

Sensor Specifications and Layout

Design Review - NA62 GTK ASIC Demonstrator Circuits
Oct. 7-8, 2008

General Parameters

Wafer specifications:

- 4" high resistivity FZ wafers
- <100> or <111>
- 4-8 kOhmcm starting material
- n-type, phosphorous doped
- thickness: 200 μm ($\pm 10 \mu\text{m}$)
- bow: <30 μm

Operation Parameters

- Depletion voltage: <30V
- Operation voltage: >300V
- Breakdown voltage:>500V
- Temperature: 5°C or less
- Radiation levels: up to $2E14 \text{ n}_{\text{eq}} \text{ cm}^{-2}$ per year
- Operation close to drift velocity saturation

Drift velocity

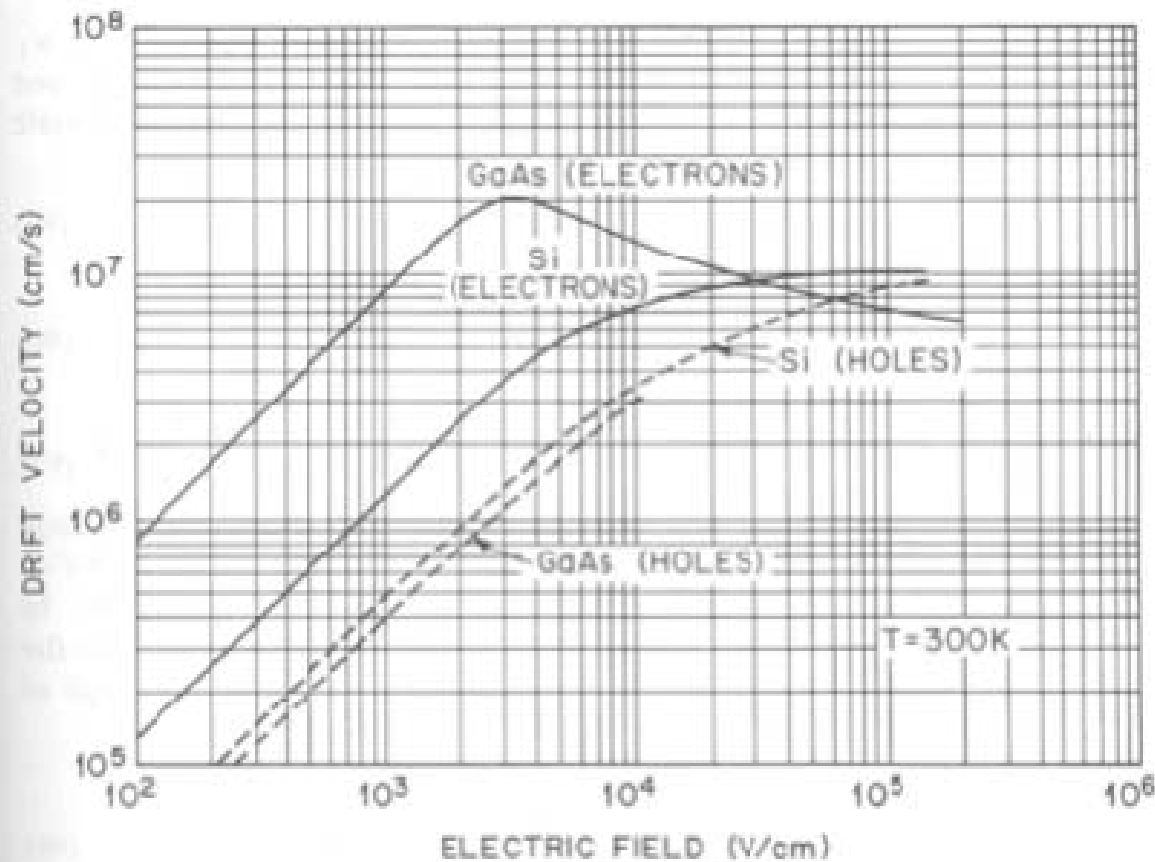


Fig. 23 Drift velocity versus electric field in GaAs and Si.^{12, 13} Note that for *n*-type GaAs, there is a region of negative differential mobility.

$E \sim 1.5-2.5E6$ V/cm

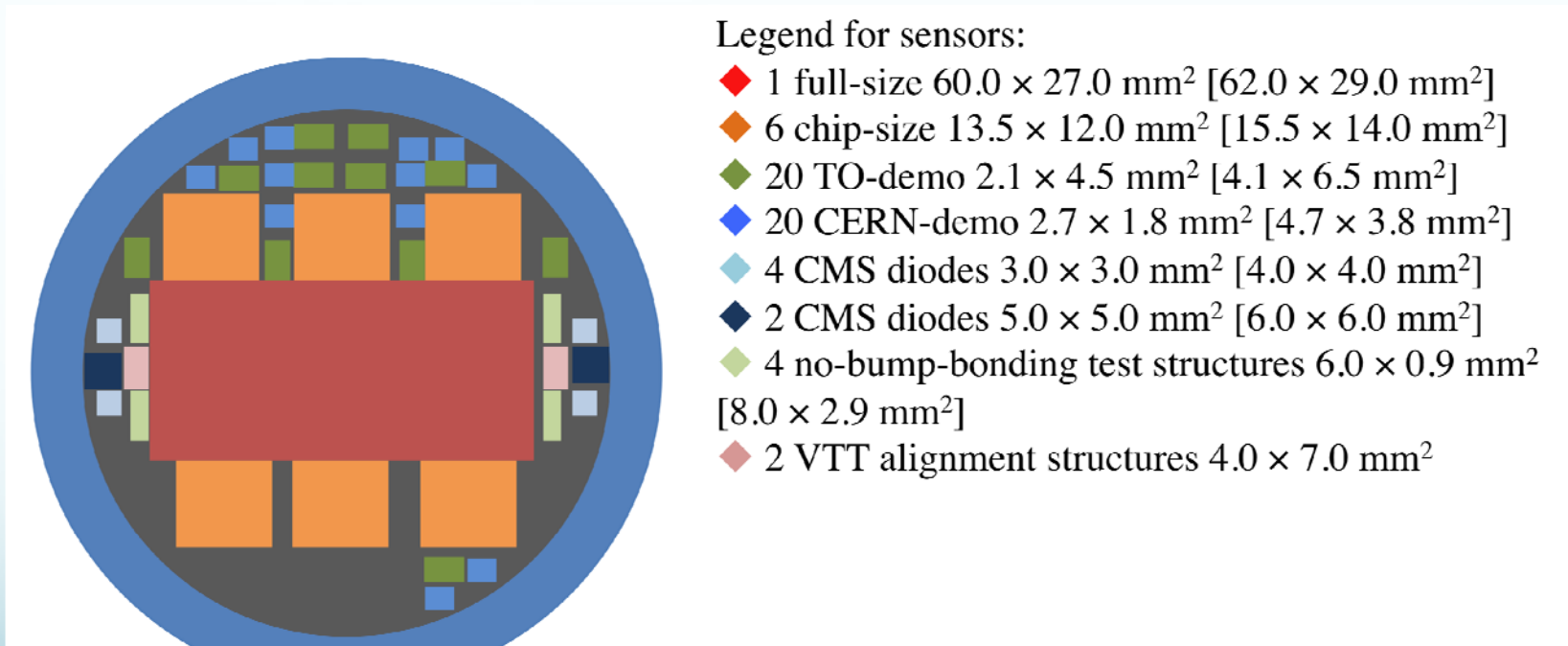
For $V \sim 300-500V$

High Voltage Operation

- Current breakdown has to occur far from the operating region (300-500V)
- Multi-guard structure
 - Test diodes from FBK irradiated to $2E14 \text{ n}_{\text{eq}} \text{ cm}^{-2}$
 - Test diodes with 4 and 12 guard rings evaluated after irradiation up to 1000 V
- Sufficient distance between last active pixel edge and scribe line
 - Suggested distance by FBK: 1 mm

Sensor Wafer Layout

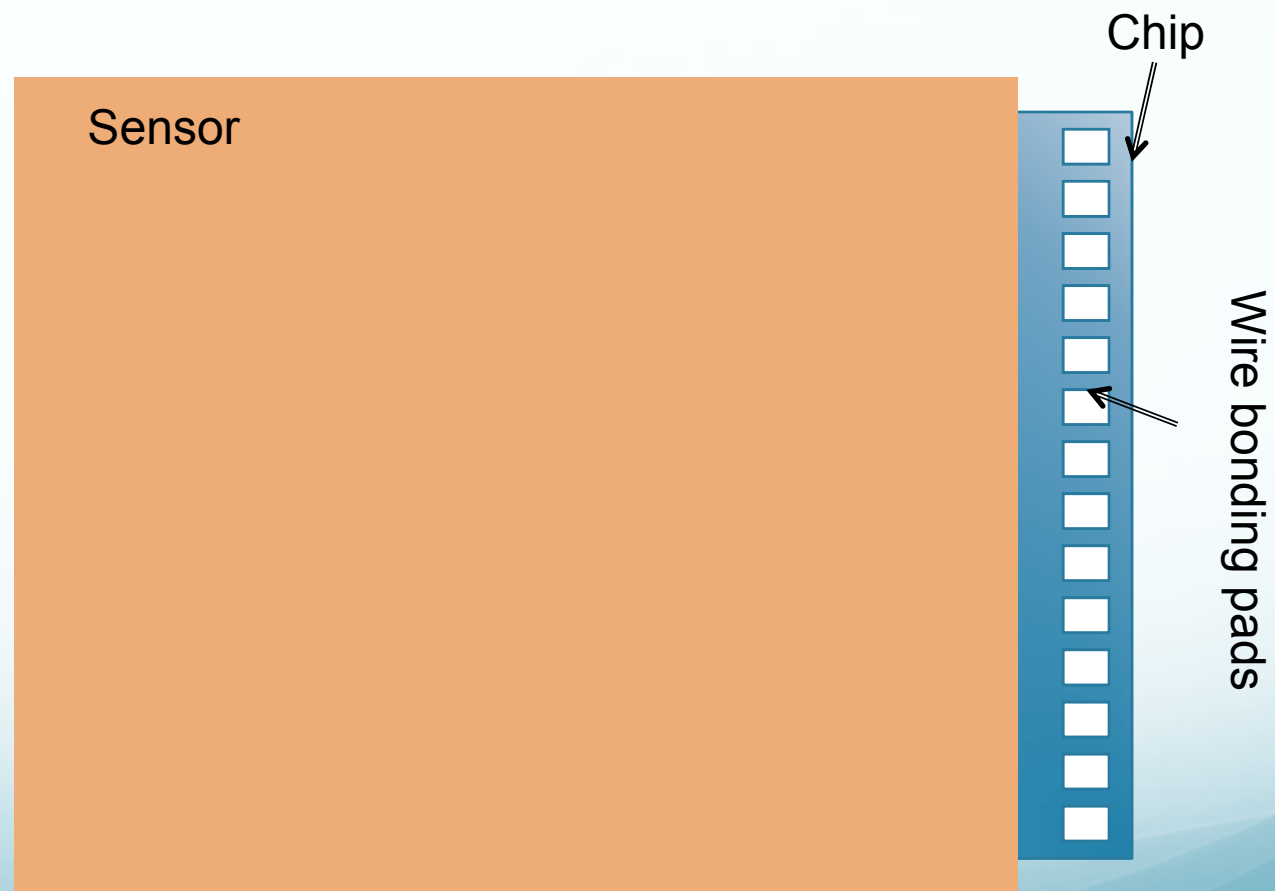
- In progress, first proposal available



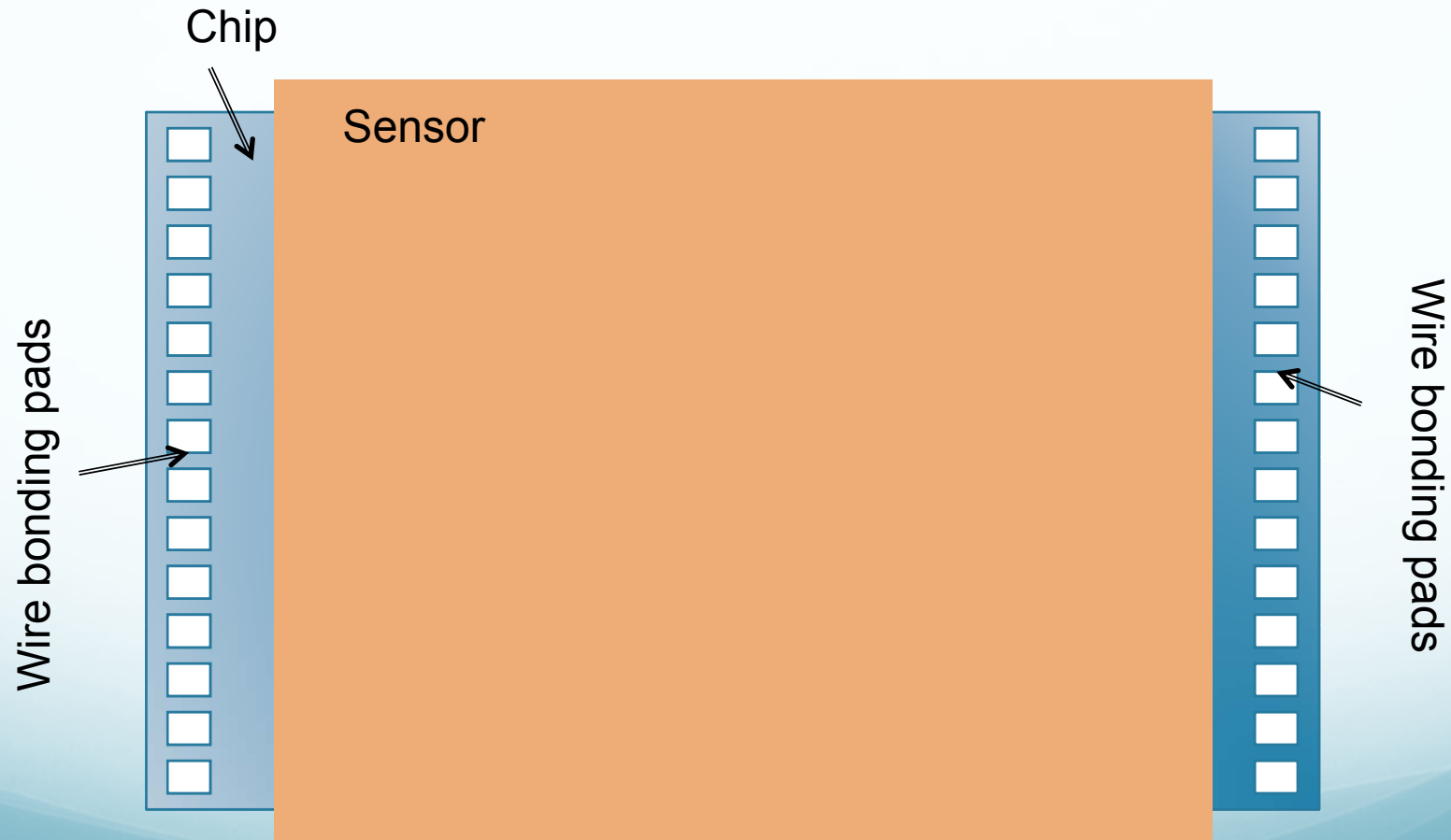
Structures per Wafer

	Name	Description	Active size
1	GTK sensor	2 x 5 pixel chip matrices (10 x 1800 pixels)	27 mm x 60 mm
2	Single chip sensor	1800 pixels	13.5 mm x 12 mm
3	TO demonstrator sensor		
4	CERN demonstrator sensor	45 pixel cells (9 x 5)	2.7 mm x 1.5 mm
5	Diode (CMS)	Test diode with multiguard structure and opening in the Al	
6	RD50 Radmon diode	Test diode with multiguard structure and opening in the Al	
7	20x3 matrix	Test structure with final size pixels, no bump bonding contacts, add opening in the central pads for laser measurements	6 mm x 0.9 mm
8	FBK test structures		
9	FC bonding test structures	Demonstrator size sensors for fc bonding tests	
10	...		

Schematic Torino Demonstrator

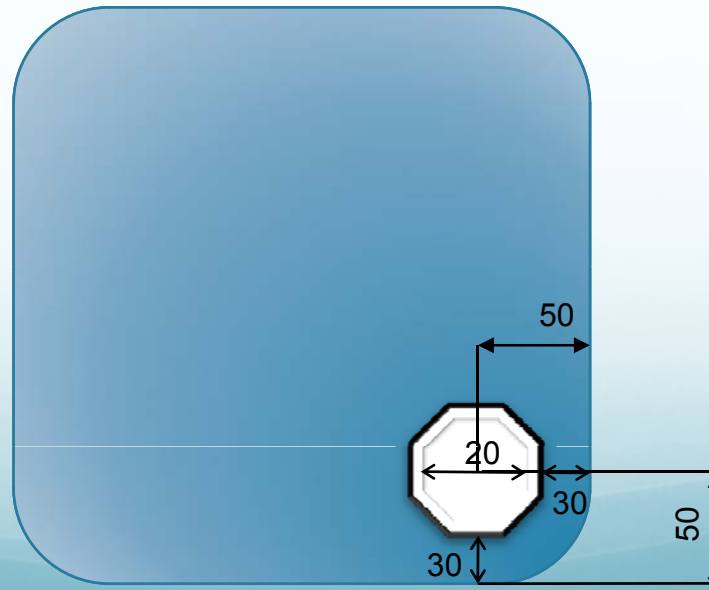


Schematic – CERN Demonstrator



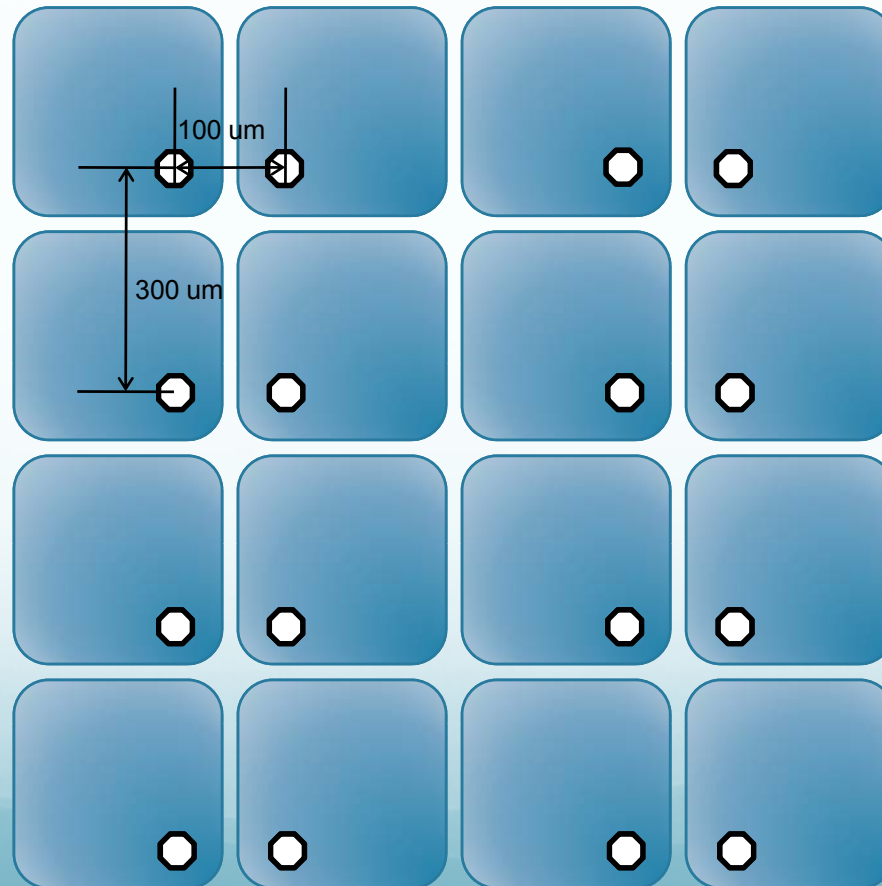
Bump Pad Layout

- Medipix/ALICE pad design
- Octagonal shape
- 26 μm diameter with 20 μm passivation opening
- Minimum distance required from pixel edge: 30 μm ->pixel center at 50 μm from the edge

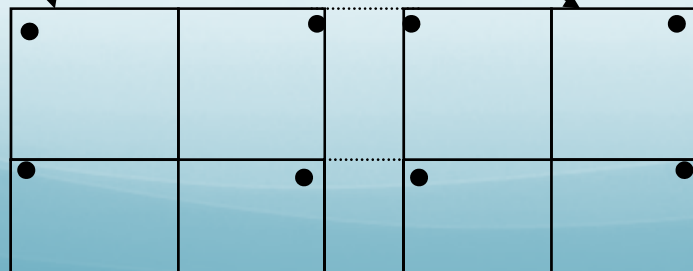
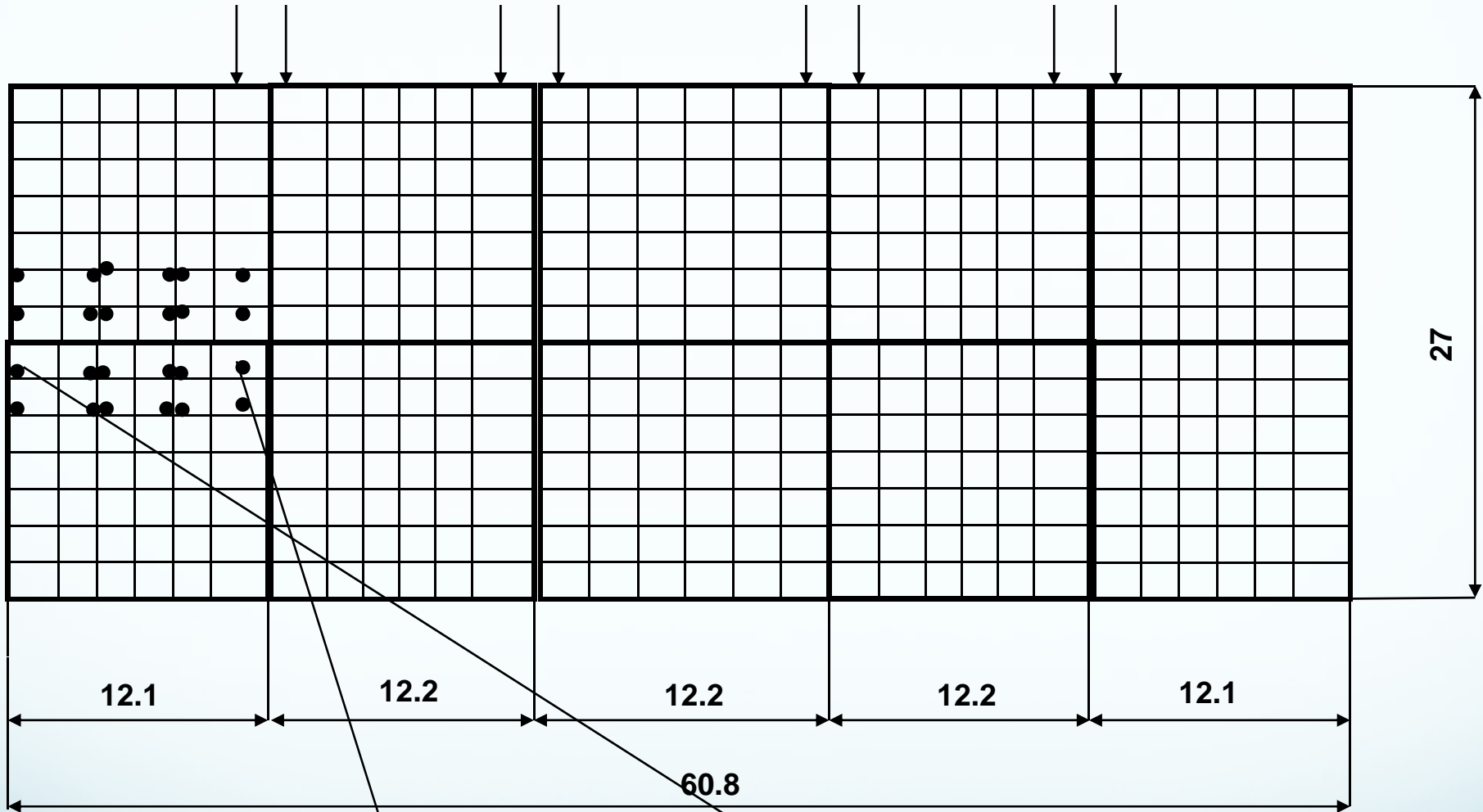


Bump Pad Arrangement

- Proposed scheme: mirrored bump pads on neighboring columns (chip layout)



400 μm instead of 300



chip bump
layout

F. Marchetto

Bump Pad Center Coordinates

- Coordinate system origin at the lower-left side corner
- i -> column number from 1 to 200
- j -> row number from 1 to 90

X Coordinates in mm

- 1-40:
 - 0.05, 0.55, 0.65, 1.15, 1.25, 1.75, ..., 11.35, 11.45, 11.95
 - -> odd: $(i-1)*0.3+0.05$ even: $i*0.3 - 0.05$
- 41-80:
 - 12.25, 12.75, 12.85, 13.35, 13.45, ..., 23.65, 24.15
 - -> odd: $(i-1)*0.3+0.25$ even: $i*0.3 + 0.15$
- 81-120:
 - 24.45, 24.95, 25.05, 25.55, 25.65, ..., 35.85, 36.35
 - -> odd: $(i-1)*0.3+0.45$ even: $i*0.3 + 0.35$
- 121-160:
 - 36.65, 37.15, 37.25, 37.75, 37.85, ..., 48.05, 48.55
 - -> odd: $(i-1)*0.3+0.65$ even: $i*0.3 + 0.55$
- 161-200:
 - 48.85, 49.35, 49.45, 49.95, 50.05, ..., 60.25, 60.75
 - -> odd: $(i-1)*0.3+0.85$ even: $i*0.3 + 0.75$

Coordinates

- X Coordinates in mm:
 - odd: $(i-1)*0.3 + 0.05 + \text{INT}(i/40)*0.2$
 - even: $i*0.3 - 0.05 + \text{INT}(i/40)*0.2$
 - INT means integer part of the ratio between i and 40
- Y Coordinates in mm:
 - 1-45:
 - 0.05, 0.35, 0.65, 0.95, ..., 12.95, 13.25
 - $\rightarrow (j-1)*0.3 + 0.05$ for $j \leq 45$
 - 46-90:
 - 13.75, 14.05, 14.35, 14.65, ..., 26.35, 26.65, 26.95
 - $\rightarrow (j-1)*0.3 + 0.25$ for $j > 45$

Outlook

- Finalize specification and wafer layout by beginning of October
- Submit information to FBK
- Meeting with FBK to discuss mask layout by beginning of November

Backup

Non-BB Teststructure

